



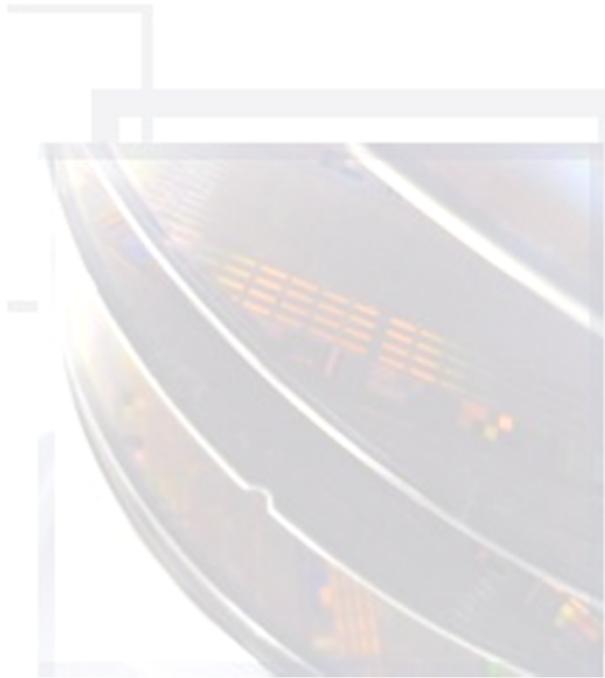
Asia and South Pacific Design Automation Conference ASP-DAC

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**Hybrid CMOS / Magnetic Process Design Kit and
SOT-based Non-volatile Standard Cell Architectures**



DIPMEM

- 
- **Introduction**
 - **Magnetic Tunnel Junction overview**
 - **Hybrid CMOS / SOT-Magnetic PDK**
 - **Hybrid non-volatile flip-flop architectures**
 - **Conclusion**

Introduction

Magnetic Tunnel Junction overview

Hybrid CMOS / SOT-Magnetic PDK

Hybrid non-volatile flip-flop architectures

Conclusion

- Adding non-volatility in ASIC
 - Reducing the power consumption
 - Improving the reliability of systems

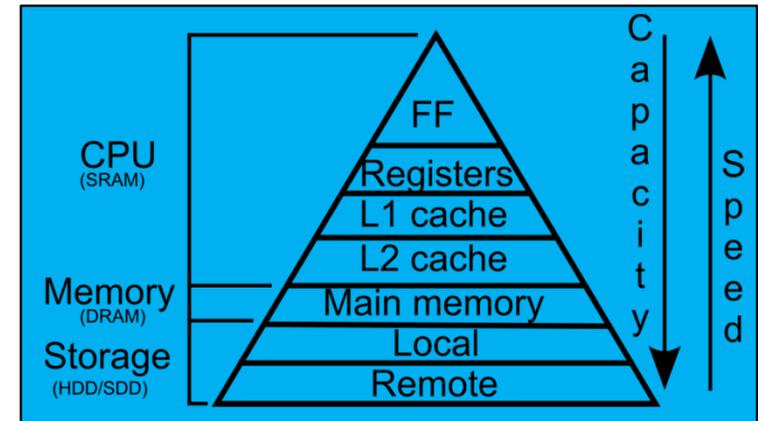


FIG. 1 : Memory hierarchy

- MTJs can be integrated at several levels of memory hierarchy
 - Memories (not addressed in the presentation)
 - Logic blocks (focus of this talk)
 - Differential reading :
1 Parallel and 1 anti-parallel

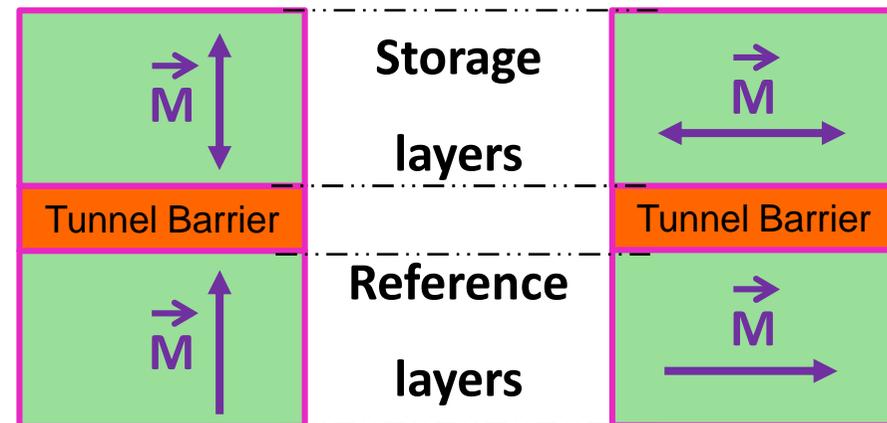
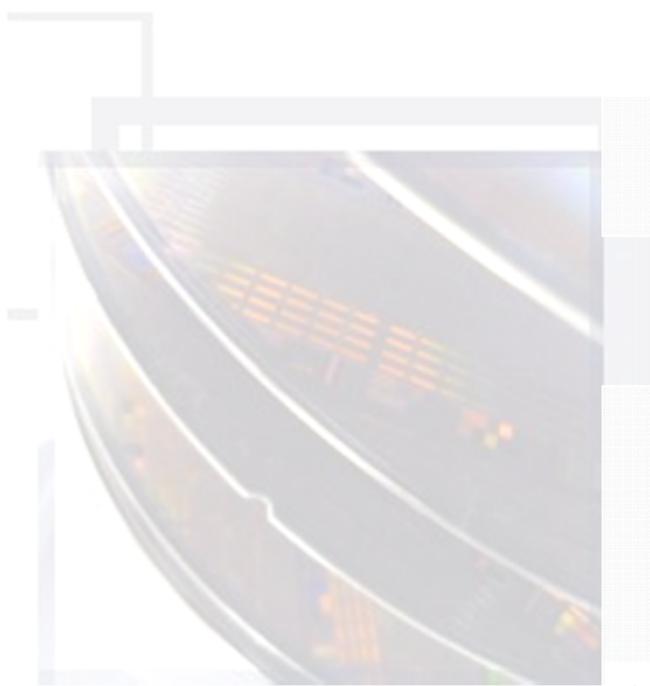


FIG. 2 : Perpendicular-to-plane and in-plane MTJ



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- ❑ First generation of Magnetic Tunnel Junction
- ❑ Writing using an external field: ~ 60 Oe
- ❑ Combination of 2 field lines selecting 1 row and 1 column.
- ❑ Reading is activated by a select transistor
- ☺ Enable to start combining spintronics and microelectronics, mature process
- ☹ Scaling, selectivity, power consumption

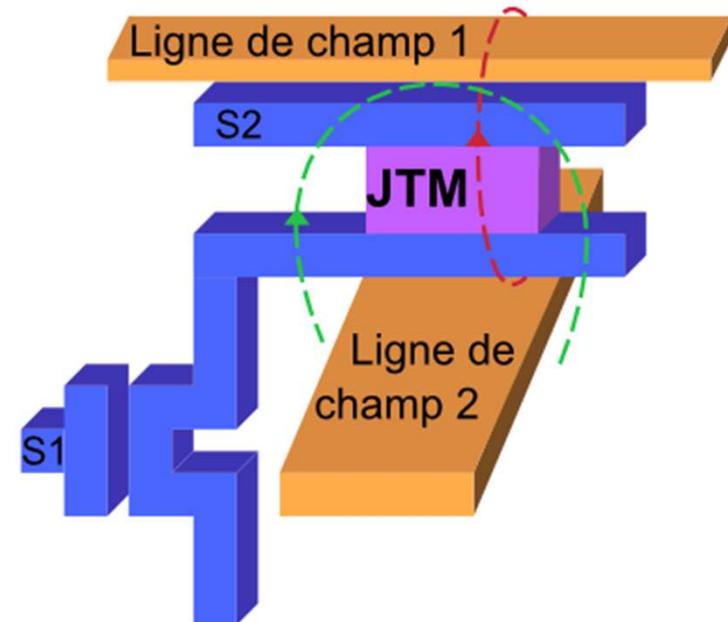


FIG. 3 : FIMS - MTJ

- Storage layer = Synthetic Anti-Ferromagnet (SAF layer) composed of 2 FM layers
- Writing using an external field: ~ 90 Oe, based on a specific sequence
- 2 field lines as standard FIMS.

- 😊 Only product commercialized

→ Everspin



- 😐 Selectivity

- 😞 Scaling, power consumption

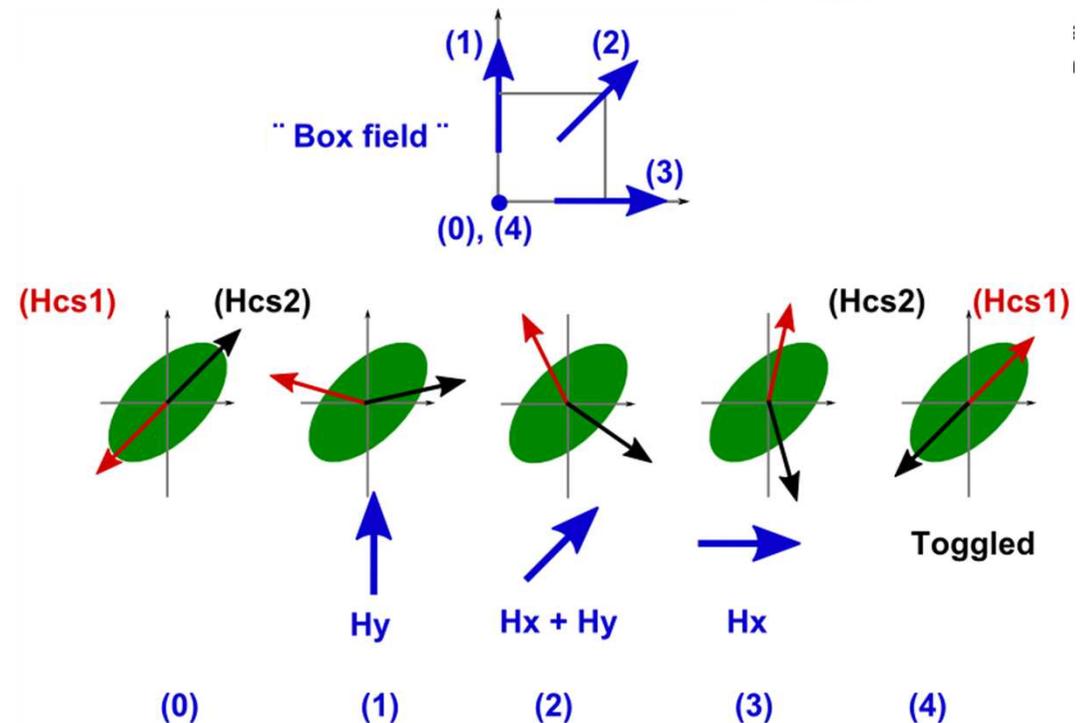


FIG. 4 : FIMS-Toggle writing mechanism

- ❑ Firstly proposed by Spintec Laboratory – France
- ❑ Industrialization by Crocus Technology 
- ❑ Stability ensured by exchange energy with an Anti Ferro Magnet (AFM)
- ❑ Writing by a reduced external field, eased by heating the MTJ.

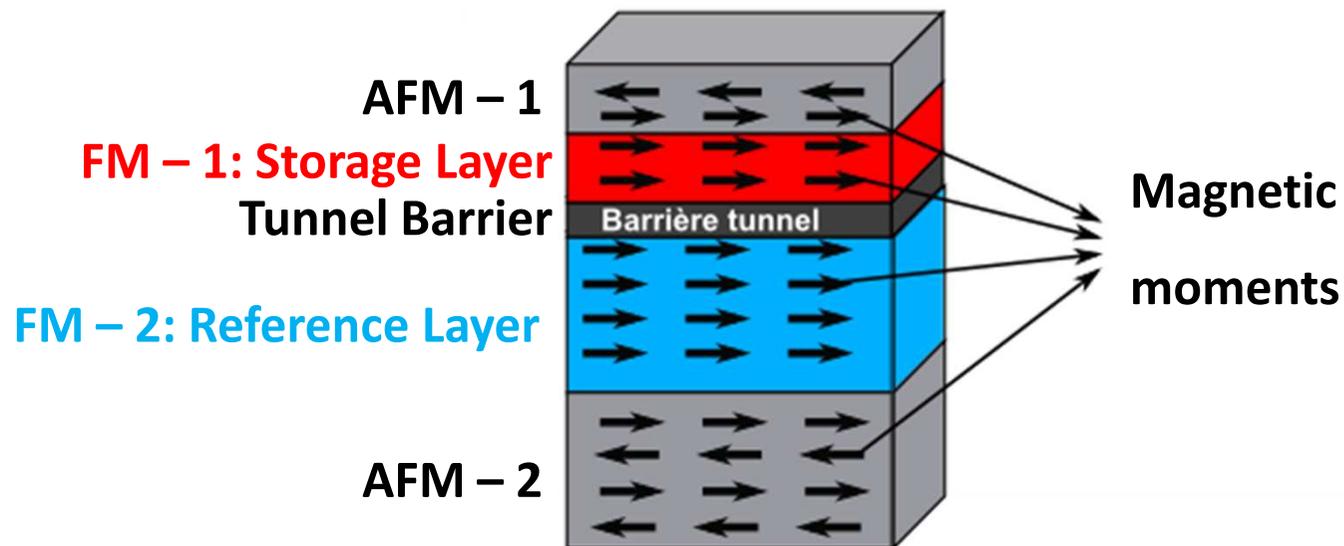


FIG. 5 : TAS - MTJ stack

☐ Only 1 field line



☐ 😊 Selectivity

☐ 😞 Scalability, reduced writing field, power consumption

☐ 😊 Thermal stability

☐ 😞 Writing speed limited by heating / cooling

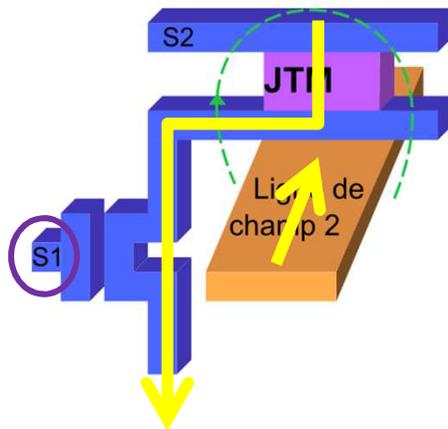


FIG. 6 : TAS - MTJ

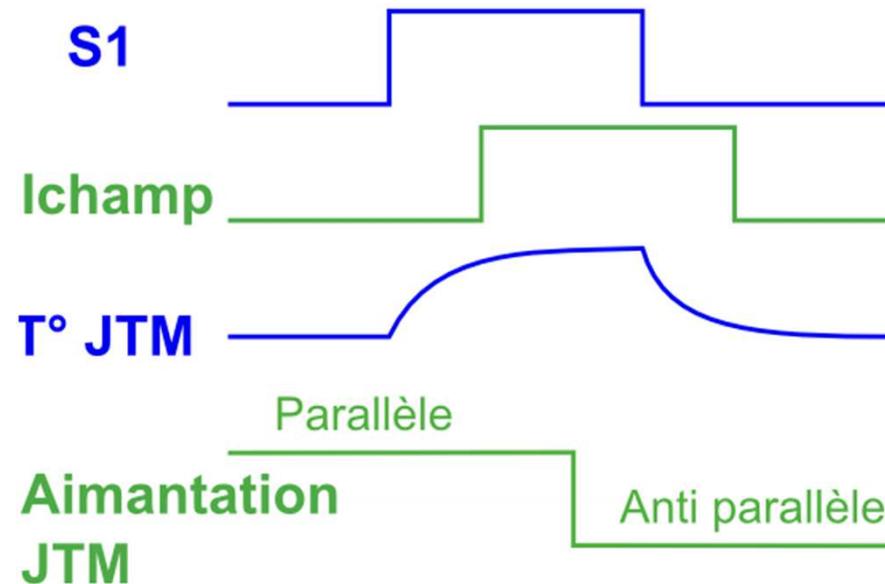


FIG. 7 : TAS writing mechanism

- ❑ Writing with spin polarized current
- ❑ In-plane or perpendicular-to-plane anisotropy

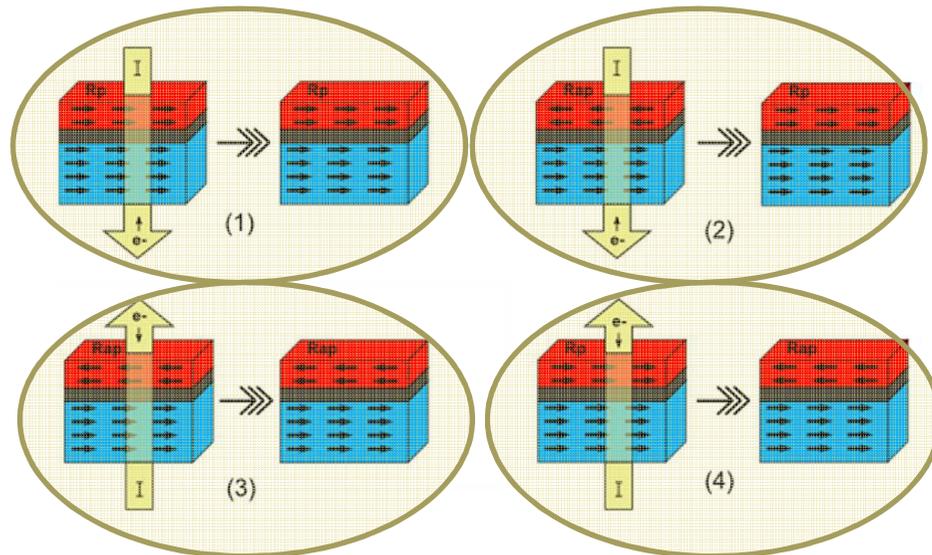


FIG. 8 : STT - MTJ writing mechanism

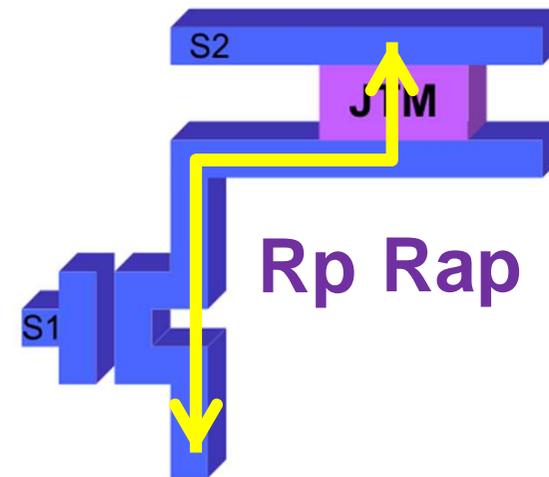


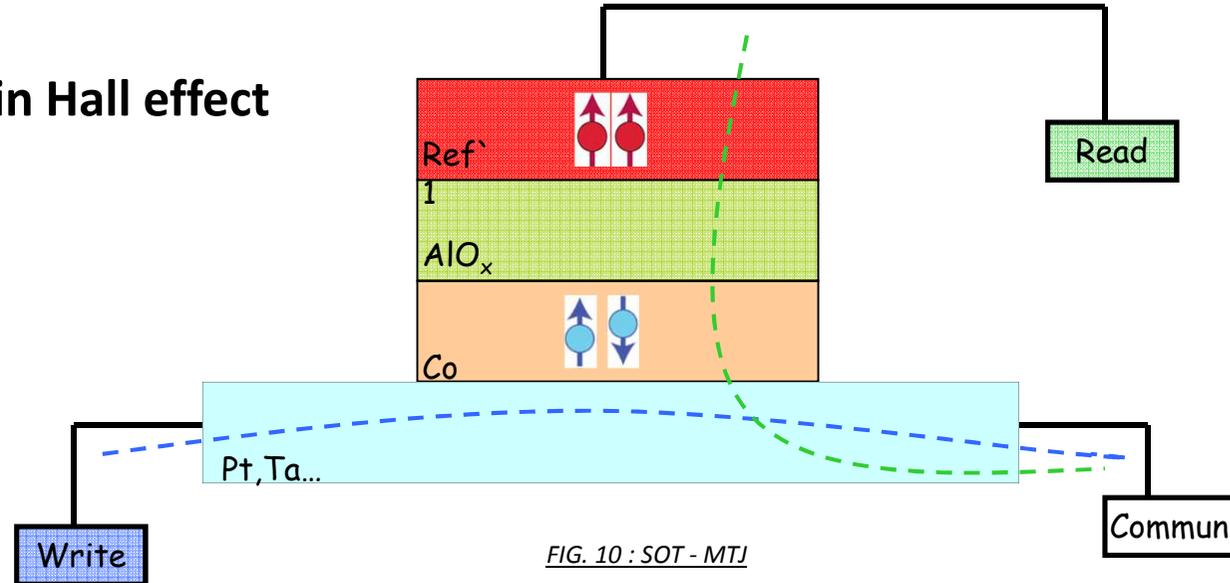
FIG. 9 : STT - MTJ

- ❑ 😊 Selectivity, low writing current, W/R high speed (~2-5 ns), density, scalability
- ❑ ➔ The current most promising MRAM technology
- ❑ 😞 Read disturb: writing during a reading phase + barrier damaging when writing, stochastic effects

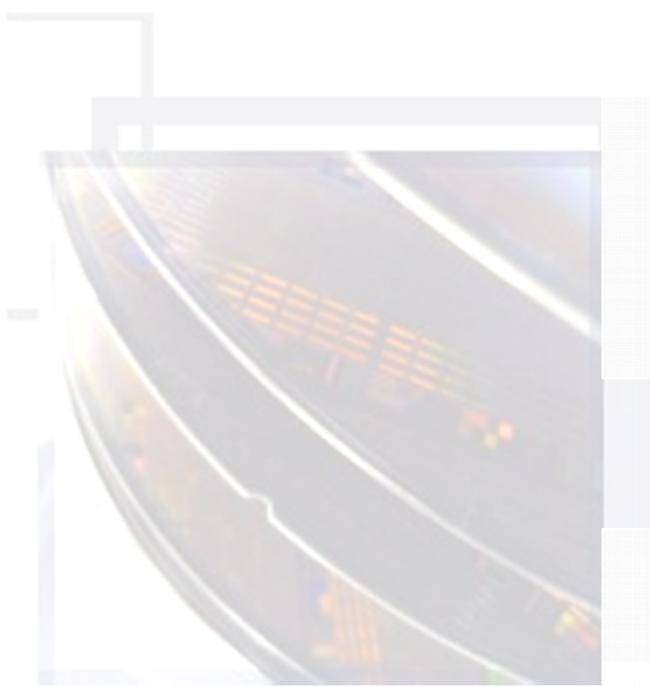
- Writing with in-plane polarized current at the interface conductor / storage layer

→ Rashba and Spin Hall effect

- 3-terminal device



- ☺ Reliability : different reading and writing path → no more read disturb and no tunnel barrier damaging, symmetrical writing P / AP.
- ☺ Ultra fast writing (~0.5-2 ns), fast reading, low writing energy, scalability
- ☹ Last MTJ generation → process under development, density depending on the architectures but can be as dense as STT



Introduction

Magnetic Tunnel Junction overview

Hybrid CMOS / SOT-Magnetic PDK

Hybrid non-volatile flip-flop architectures

Conclusion

- ❑ Need full hybrid CMOS / magnetic Process Design Kit (PDK)
- ❑ → Electrical simulation model: developed
- ❑ → Schematic environment
- ❑ → Layout environment
- ❑ → Design Rule Checking: DRC
- ❑ → Layout Vs Schematic: LVS
- ❑ → Parasitic extraction

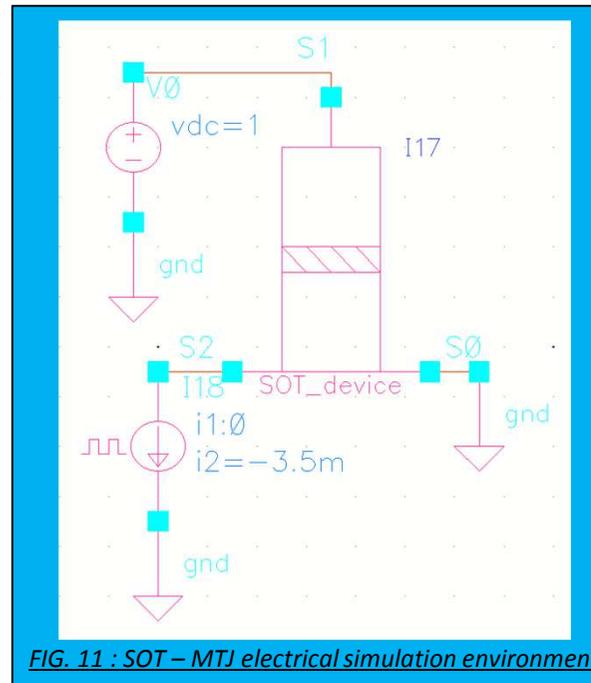


FIG. 11 : SOT – MTJ electrical simulation environment

CMOS
Layers

Magnetic
Layers

LSW	
Sort	Edit
metal5	drawing
DK_process_013u_MTJ	
Show Objects	
AV	NV AS NS
v4 drawing	
v4	pin
metal5	drawing
metal5	posPS
metal5	negPS
metal5	fringe0
metal5	pin
metal5	pintext
metal5	markerR
metal5	markerL
metal5	markerC
metal5	markerLS
metal5	markerLA
metal5	markerZ
metal5	annotate
mSlot	drawing
vial_mag	drawing
LIGPTHEM	drawing
LIGPTHEM	pin
PTHEM	drawing
via2_mag	drawing
metal5_bis	drawing
metal5_bis	pin
MTJPLUS	pin
v5	drawing
v5	pin
metal6	drawing
metal4	net
v4	net
metal5	net
vial_mag	net
LIGPTHEM	net
PTHEM	net
via2_mag	net
metal5_bis	net
MTJPLUS	net
v5	net
metal6	net
nvarac	drawing

FIG. 12 : Hybrid LSW

- ❑ Verilog A language: compatible with all electrical simulators (Spectre, Eldo, ...)
- ❑ Behavioral and very accurate versions, based on physics
- ❑ Composed of 2 modules: * Landau–Lifshitz–Gilbert equations (LLG)

* Tunnel Magneto Resistance variation (TMR)

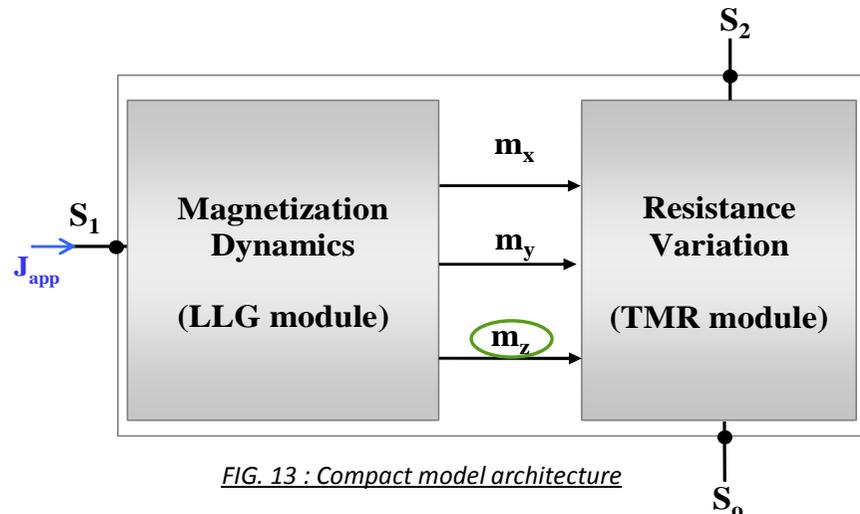


FIG. 13 : Compact model architecture

- ❑ Current density applied as input (J_{app})
- ❑ Resistance value and variation as output.

- ❑ **LLG Module**
 - Crystalline anisotropy field
 - Demagnetizing field
 - Rashba field
 - Spin Hall Effect field
 - External applied field

$$\vec{H}_{eff} = \vec{H}_k + \vec{H}_d + \vec{H}_R + \vec{H}_{SHE} + \vec{H}_a$$

- ❑ **TMR Module (Tunnel Magneto Resistance)**
 - Magnetization (Mx, My, Mz) from LLG as inputs
 - Resistance variation as output
 - Gives the dynamic resistance of the SOT-MTJ: essential for logic design
 - Jullière, Slonczewski, Brinkman and Simmons's theory (MR, tunneling...)
 - TMR depends on the voltage applied to the SOT-MTJ: very important effect for designers, especially for the reading phases (TMR₀ lowered)

Validation of the dynamic behavior

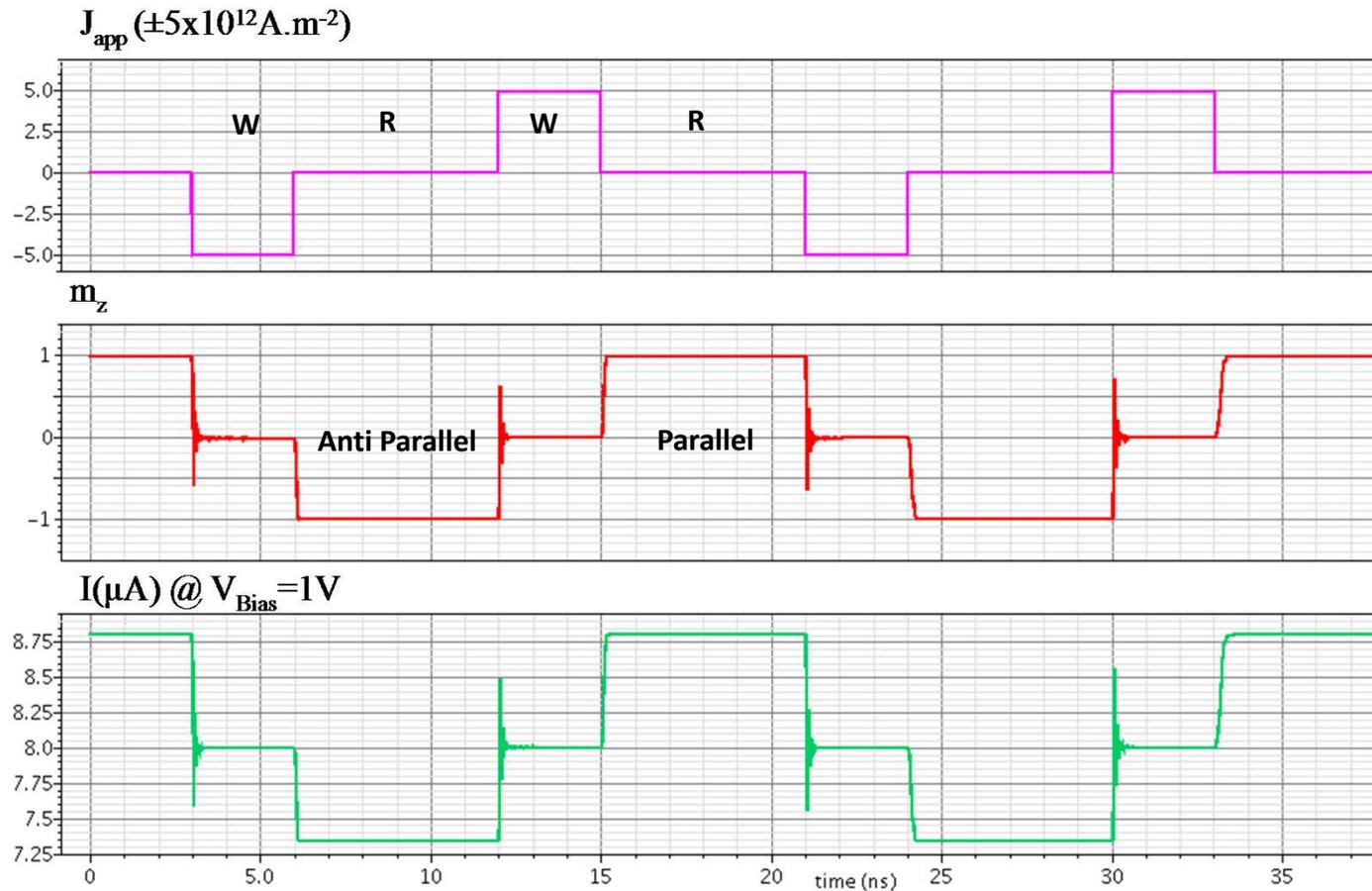


FIG. 14 : Validation of the magneto resistance variation according to current pulses or MTJ states

➔ Complete studies based on several effects are possible

Electrical simulation without external field ($H_a = 0$)

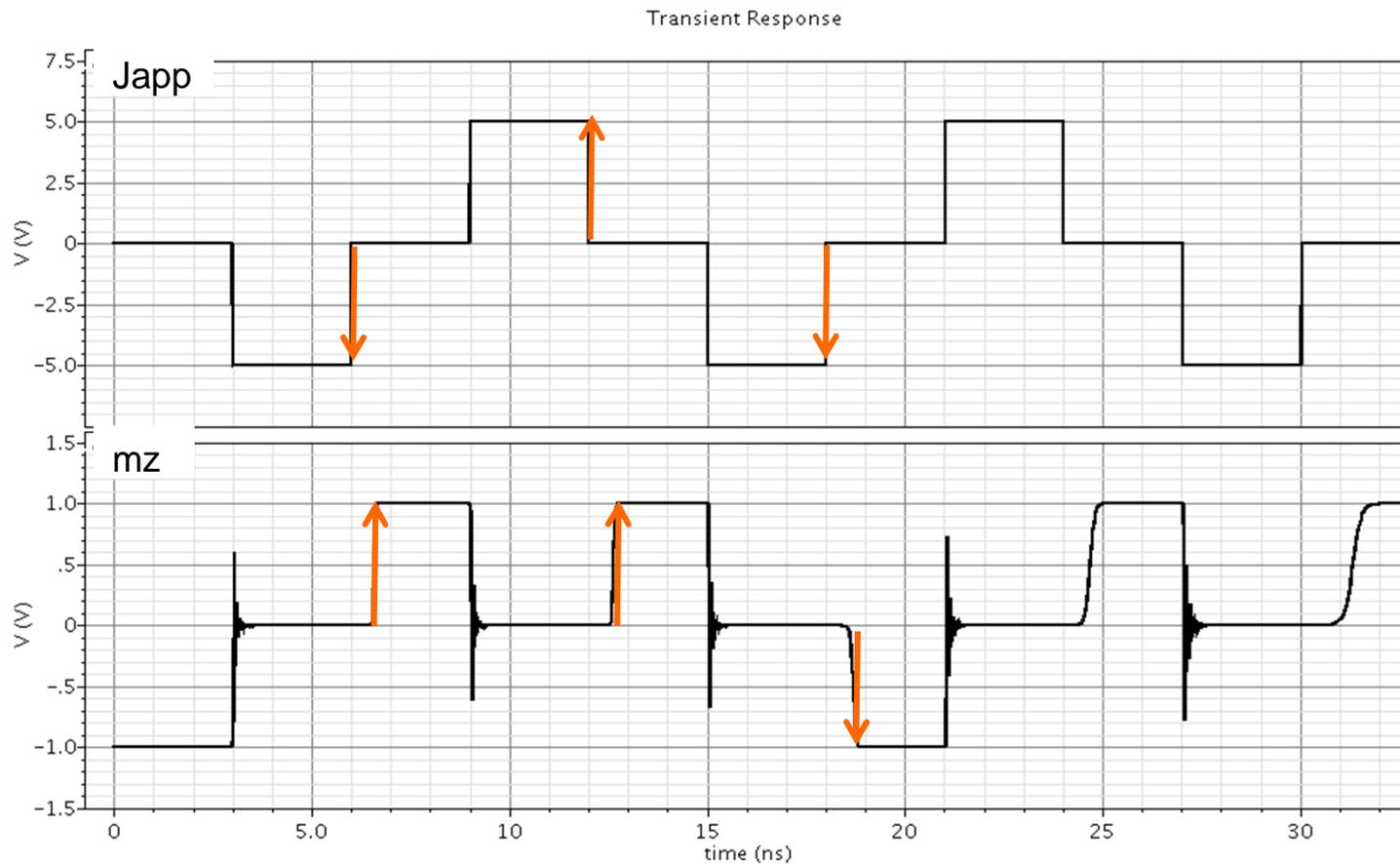


FIG. 15 : Influence of the external field

➔ Without external field the magnetization switching is random

Electrical simulation with external field ($H_a \neq 0$)

3ns pulse, $J_{app}=5E12$ A/m², $H_{ax}=-5$ mT

Transient Response

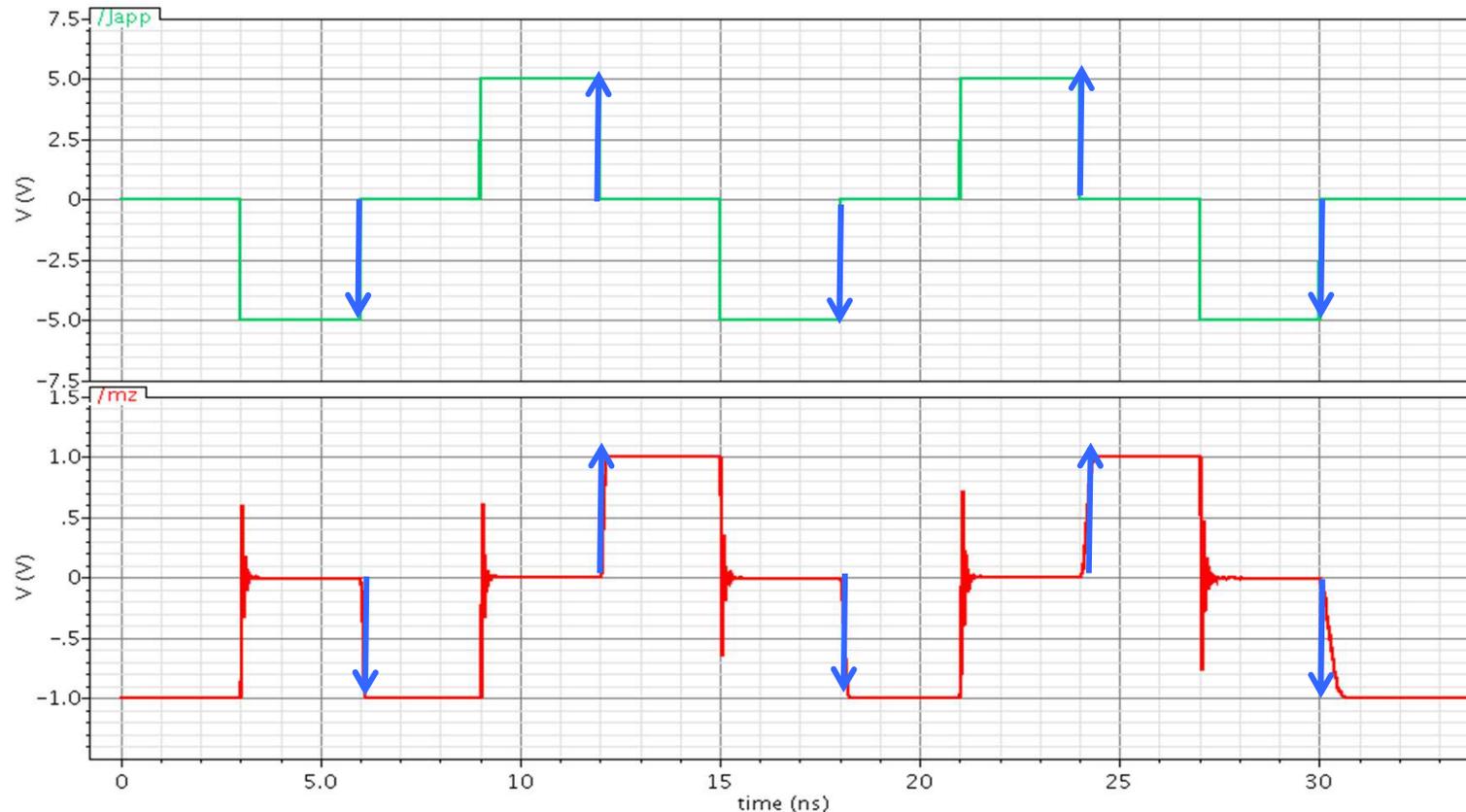


FIG. 16 : Influence of the external field amplitude

➔ With an external field the magnetization switching is deterministic. It depends on its orientation ($H_a > 0$ or $H_a < 0$)

Electrical simulation with an external field ($H_a \neq 0$)

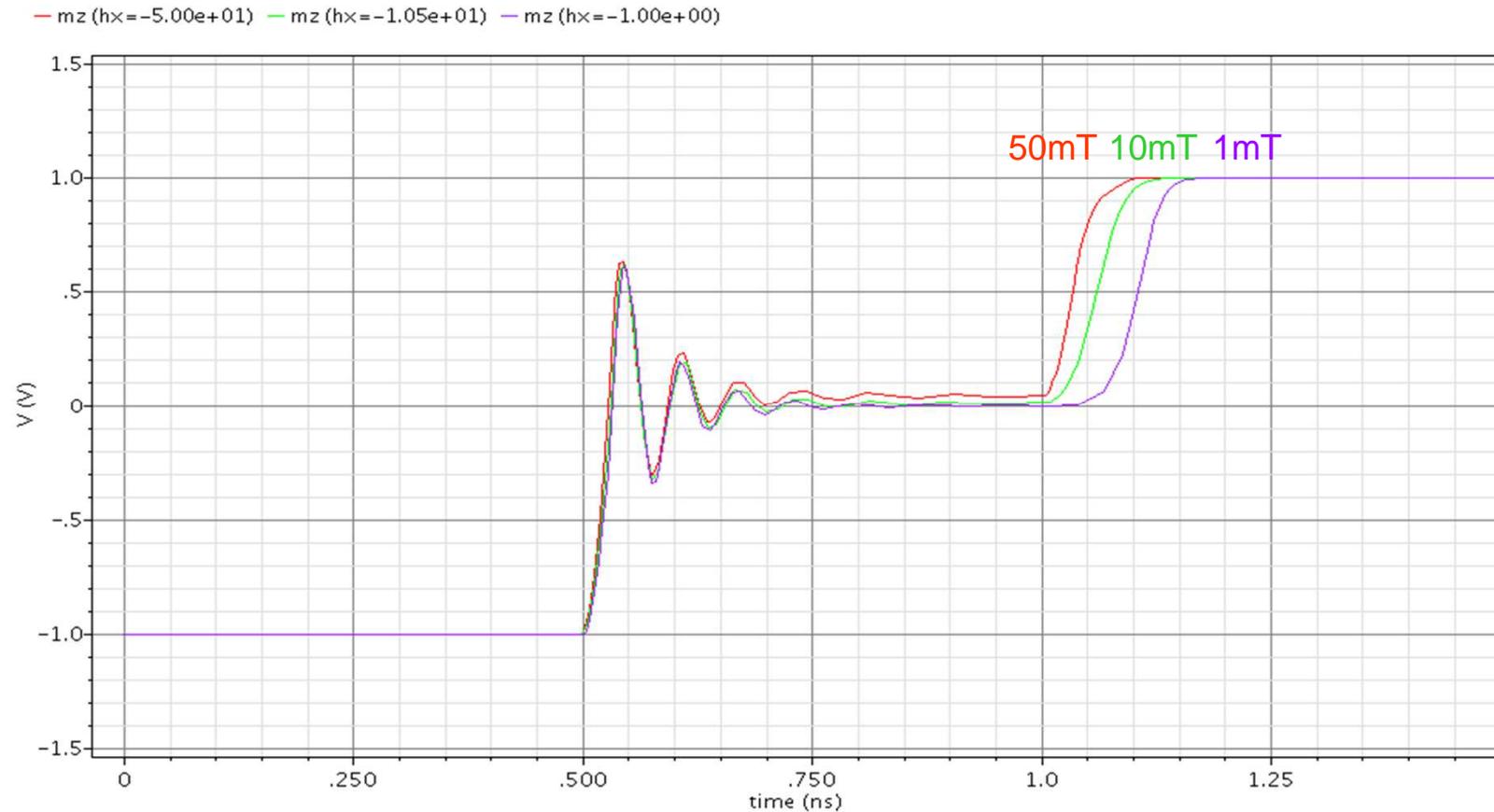


FIG. 17 : Influence of the external field amplitude

➔ The higher the external field, the faster the magnetization switching

Variation of J_{app} from $1 \cdot 10^{12} \text{ A/m}^2$ to $8 \cdot 10^{12} \text{ A/m}^2$

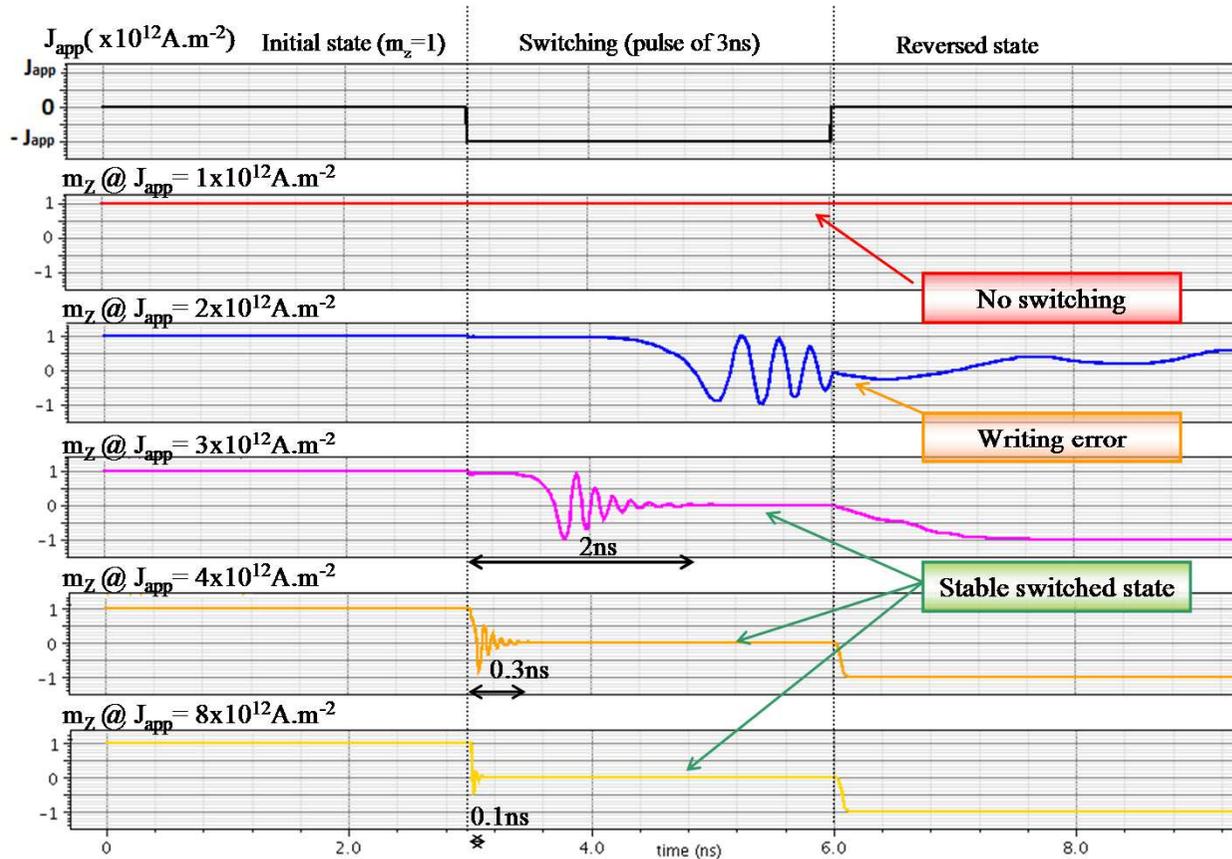


FIG. 18 : Evolution of m_z according to the current density J_{app}

➔ The higher writing current density, the faster the magnetization switching

Variation of pulse width from 3ns to 12ns

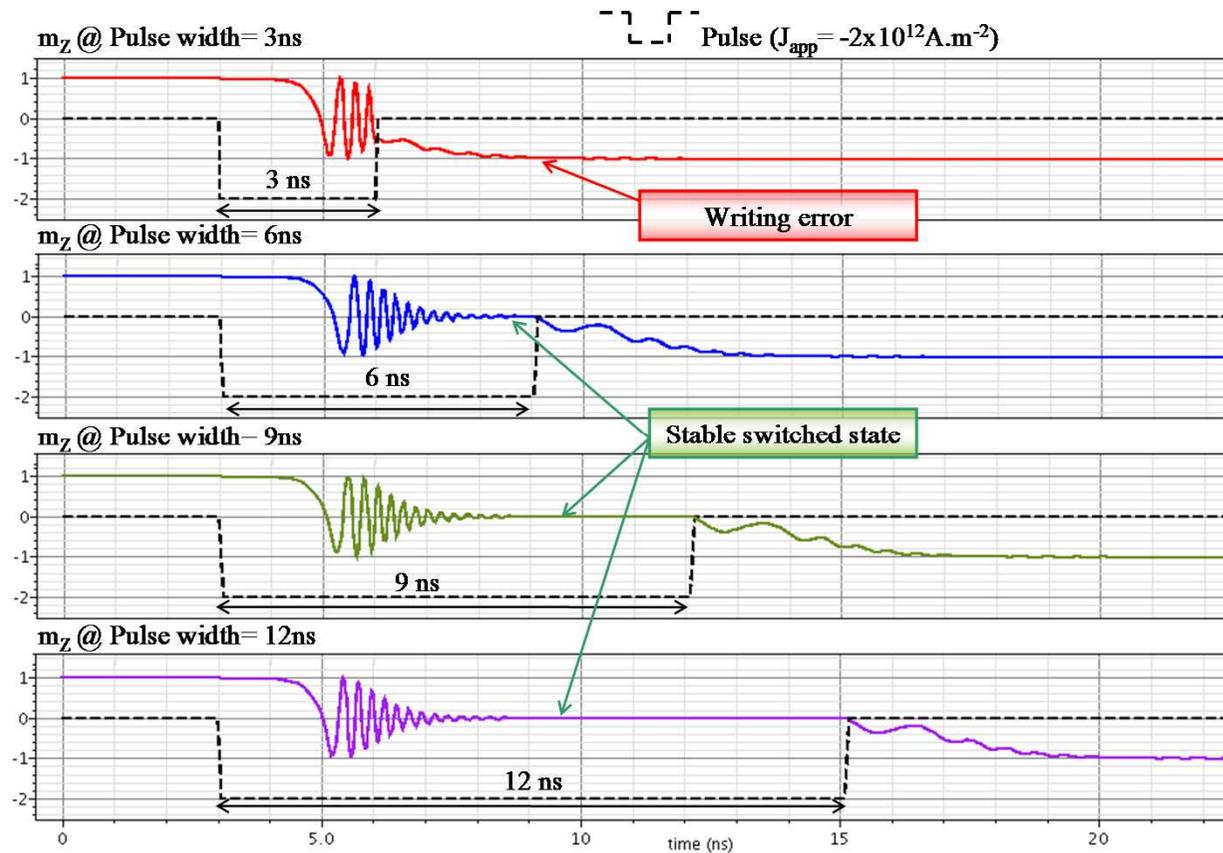
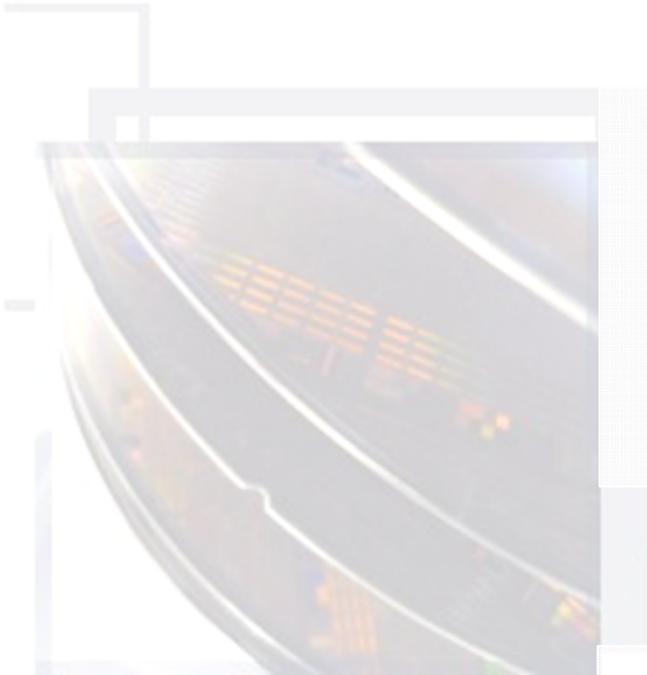


FIG. 19 : Evolution of m_z according to the pulse width @ $J_{app} = -2 \times 10^{12} \text{ A.m}^{-2}$

➔ The larger the writing pulse, the safer the magnetization switching



Introduction

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Hybrid non-volatile flip-flop architectures

Conclusion

- Adding MTJ in the logic can:

- Ease the power gating technics
- Reduce the power consumption
- Quasi “zero” standby leakage
- Instant on / normally off

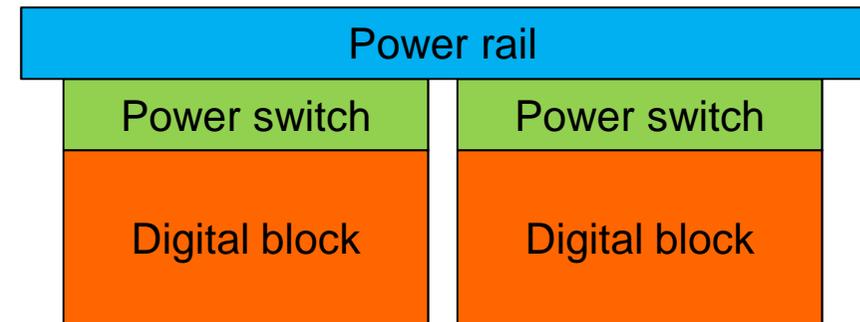


FIG. 20 : Digital floorplan

- Increase the reliability of systems

- Save / restore the flip-flop outputs
- Store a configuration in a register file
- **Need of non-volatile flip-flops**

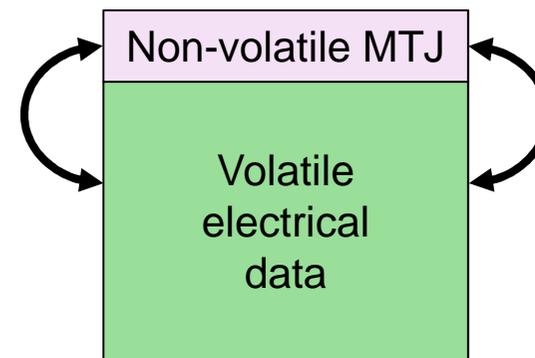
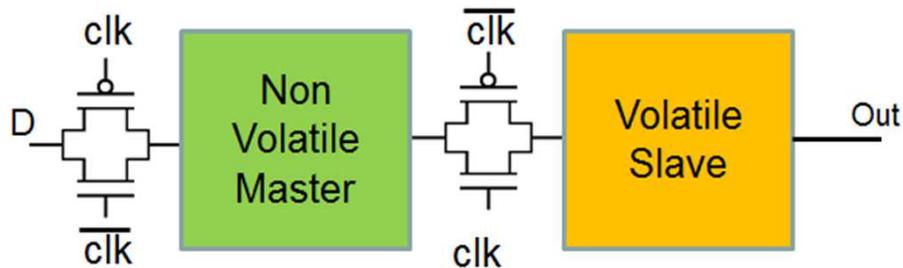


FIG. 21 : Electrical and magnetic data exchange

Non-volatility within the master

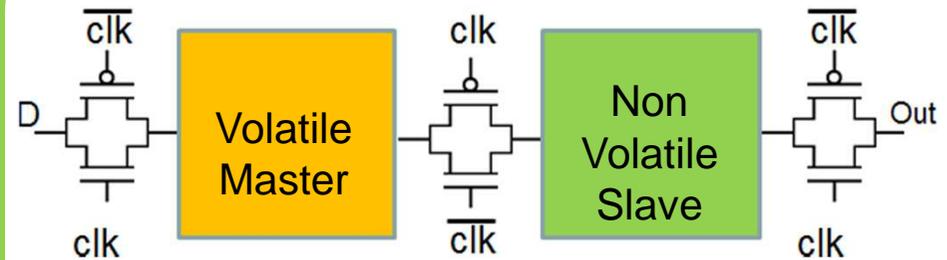


The save and restore phases can be done between 2 clock edges. The flip-flop output is always valid.



The input capacitance can be quite high depending on the SOT-MTJ features (large transistors for writing) → slower behavior

Non-volatility within the slave



The flip-flop capacitance input is the same as a CMOS flip-flop → the speed CMOS speed is preserved



Need two additional pass-gates cell to disconnect the flip-flop from the following blocks of the IP.

FIG. 22 : non-volatile flip-flop principle

Hybrid non-volatile latch: TAS based

- PMOS Low V_t ; NMOS High V_t
- 2 TAS-MTJ \rightarrow differential reading
- 2 additional PMOS for writing (2 phases)

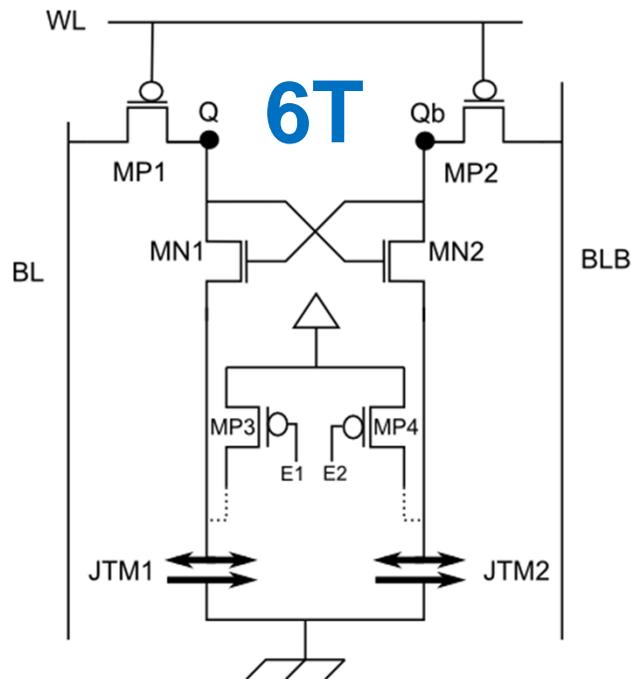


FIG. 24 : non-volatile 4T load less latch with writing transistors

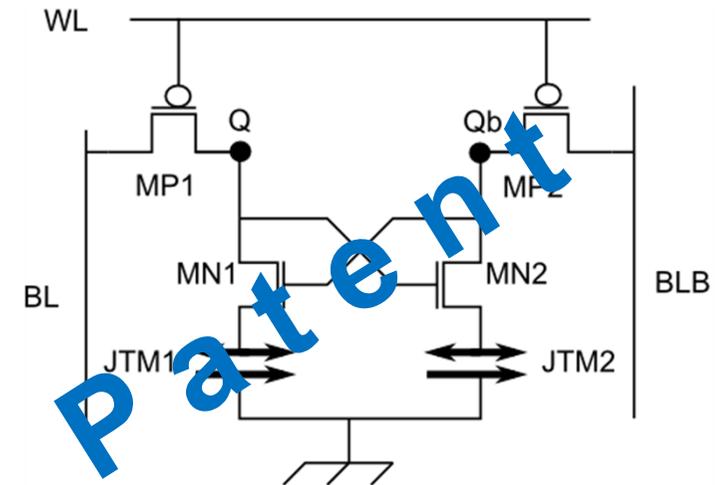


FIG. 23 : non-volatile 4T load less latch

4T Load less SRAM based

- ❑ ~~2 additional PMOS for writing~~: same writing and reading path
- ❑ Specific writing sequence

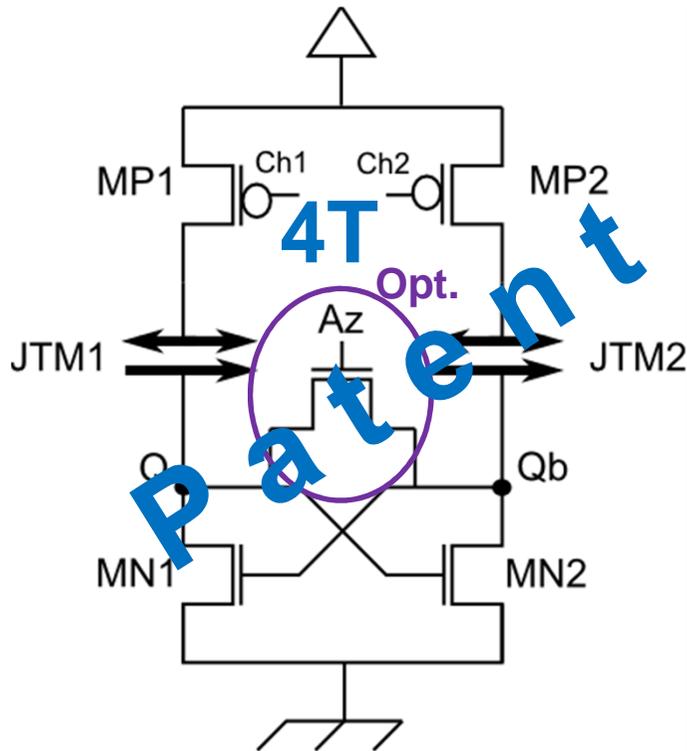


FIG. 25 : non-volatile 4T load less latch with no additional writing transistors

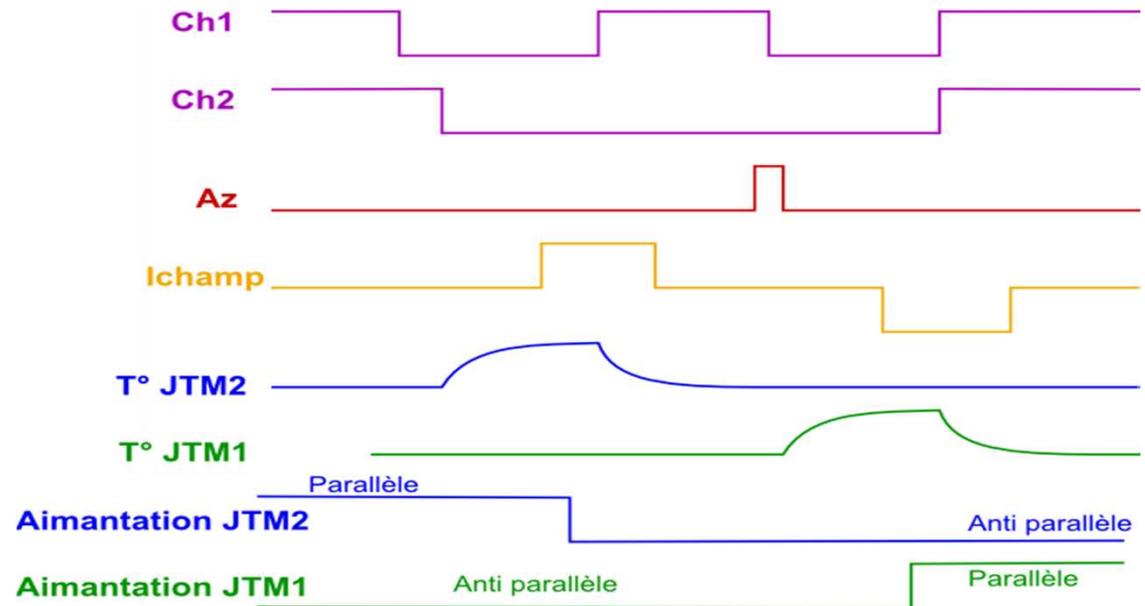


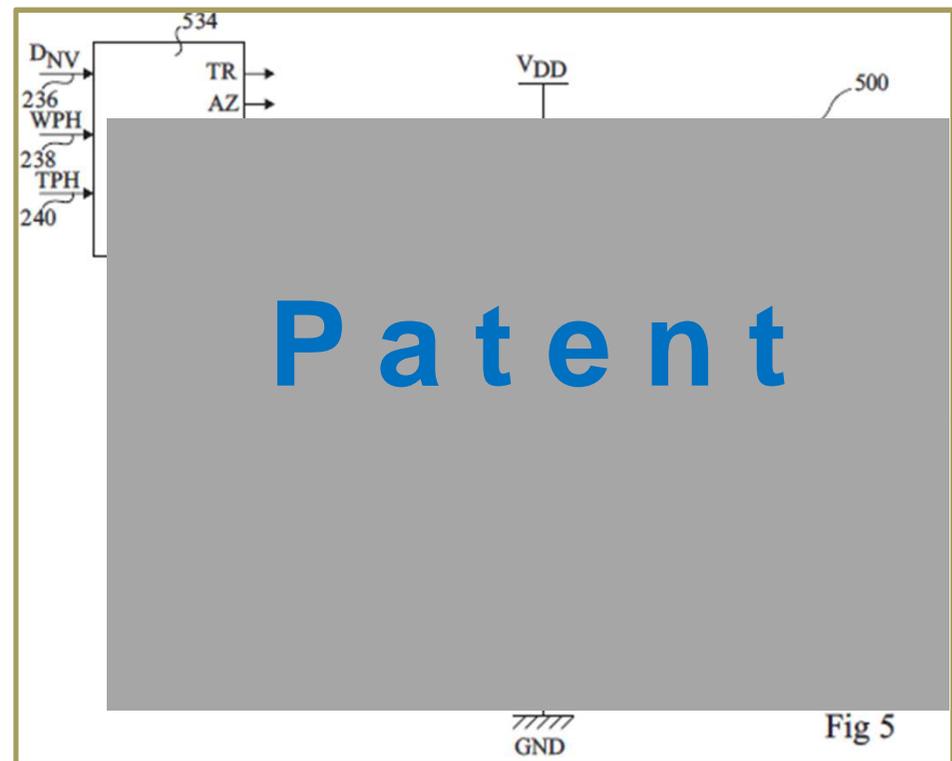
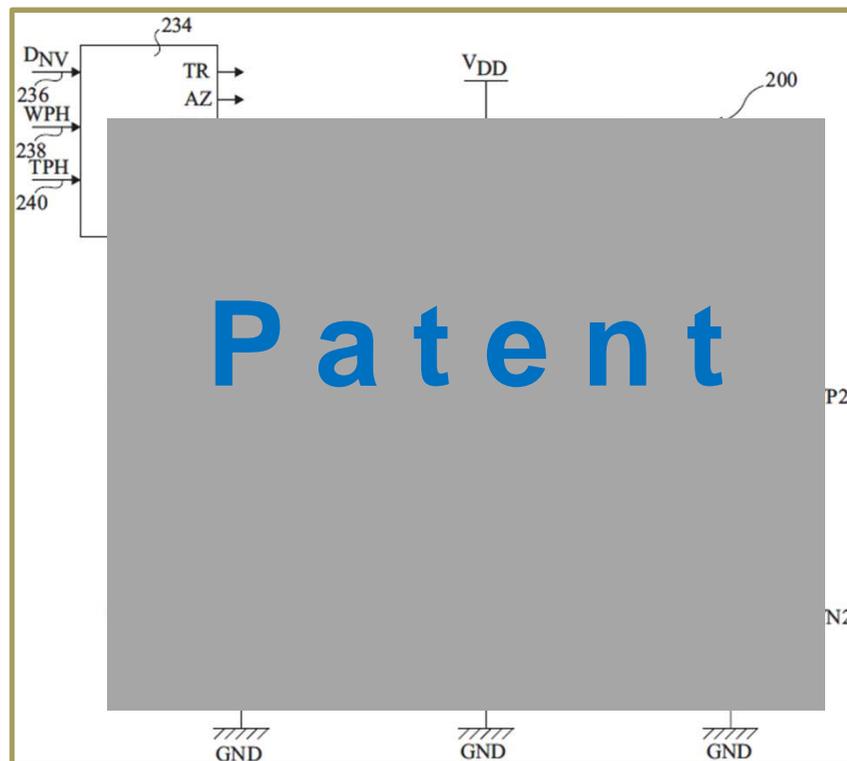
FIG. 26 : non-volatile 4T load less latch with no additional writing transistors chronogramme

❑ 😊 Very dense

❑ 😞 Speed (2 phases)

Hybrid non-volatile latch: STT based

- ❑ Cross-coupled based
- ❑ High V_t and Low V_t transistors
- ❑ Dense architecture
- ❑ Both CMOS and Magnetic behavior
- ❑ Simple control logic
- ❑ Denser architecture
- ❑ Use of body biasing in FD-SOI technology → number of transistors reduced



Hybrid non-volatile latch: SOT based

Cross-coupled based latch: validated by electrical simulation using the compact model

SOT-MTJ

Writing



Patent

FIG. 27 : Cross-coupled-based non-volatile latch



Dense architecture



Hvt and Lvt transistors,
higher standby leakage

SRAM based latch: validated by electrical simulation using the compact model

SOT-MTJ

Writing circuit



Patent

FIG. 28 : SRAM-based non-volatile latch



Well know architecture,
stable, few standby leakage



Need more transistors.

Optimized SRAM based latch: use of precharge

Patent

FIG. 29 : Optimized SRAM-based non-volatile latch



Same as SRAM-based + speed
increased, reliability



Need more transistors.



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■ **Conclusion**

- ❑ **Very good knowledge on the MTJs physics within Spintec**
- ❑ **Able to develop compact model for electrical simulation**
- ❑ **Full hybrid CMOS / Magnetic Process Design Kit currently under development**
- ❑ **Enable process improvement according to the simulation study**
- ❑ **Many flip-flops architectures proposed for all MTJ generations**

FUTUR WORK

- ❑ **Integrate these flip-flops within digital block and / or higher design level**
- ❑ **Design more complex ASICs**



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This work has been partially funded by the **European Commission under the spOt project** (grant agreement n318144) in the framework of the Seventh Framework Program, and from the **French National Research Agency (ANR) under the DIPMEM project** (contract ANR-12-NANO-0010) in the framework of the P2N program.



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! Thanks !

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